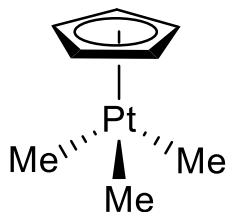


Catalog # 78-1300 (Trimethyl)cyclopentadienylplatinum(IV), 99%



Thermal Behavior:

- Melting point 104-104.5°C [1]
- Sublimation at 25°/10⁻² Torr [2]
- Vapor pressure: 0.05 Torr/25°C [1, 3,4]

Technical Notes:

1. CVD precursor for platinum thin film deposition [3,4]
2. Used for deposition of Pt nanoparticle using CVD method [6-7]

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Pt	CVD	25°C	10 Torr	H ₂	180°C	3-5
Pt	CVD	70°C	AP	H ₂	350°C	7

References:

1. [J. Organomet. Chem. 1970, 24, 501](#)
2. [Z. Naturforsch. B, 1963, 18, 507](#)
3. [Appl. Phys. Lett. 1988, 53, 1591](#)
4. [Chem. Mater. 1992, 4, 162](#)
5. [Chem. Mater. 1991, 3, 677](#)
6. [J. Mater. Chem., 2006, 16, 2464](#)
7. [ECS Trans. 2009, 25, 763](#)